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8317-091-999APPLICATION NO.
09/903,064

APPLICANT

Small, et al.

FILING DATE
July 10, 2001

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11-7-01

LIST OF REFERENCES CITED BY APPLICANT
(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

DEC 31 2001

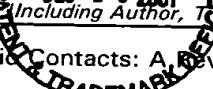
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
S	AA	6,048,406	4/11/00	Misra et al.	134	1200	
	AB	5,981,454	11/9/99	Small	510	175	
	AC	5,972,862	10/26/99	Torii et al.	510	175	
	AD	5,885,477	3/23/99	Rasmussen et al.	252	79.2	
	AE	5,792,274	8/11/98	Tanabe et al.	134	1.3	
	AF	5,709,756	1/20/98	Ward et al.	134	1.3	
	AG	5,705,089	1/6/98	Sugihara et al.	252	79.1	
	AH	5,672,577	9/30/97	Lee	510	175	
	AI	5,645,737	7/8/97	Robinson et al.	216	99	
	AJ	5,630,904	5/20/97	Aoyama et al.	438	669	
	AK	5,603,849	2/18/97	Li	216	99	
	AL	5,571,447	11/5/96	Ward et al.	510	206	
	AM	5,563,119	10/8/96	Ward	510	176	
	AN	5,560,857	10/1/96	Sakon et al.	510	175	
	AO	5,181,985	1/26/93	Lampert et al.	156	635	
	AP	5,129,955	7/14/92	Tanaka	134	2	
	AQ	4,770,713	9/13/88	Ward	134	38	
	AR	4,744,834	5/17/88	Haq	134	38	
	AS	4,508,591	4/2/85	Bartlett et al.	156	659.1	
	AT	4,428,871	1/31/84	Ward et al.	252	542	
	AU	4,403,029	9/6/83	Ward, Jr. et al.	430	258	
	AV	4,401,747	8/30/83	Ward, Jr. et al.	430	258	
	AW	4,395,479	7/26/83	Ward et al.	430	258	
	AX	3,592,773	7/13/71	Muller	252	79.3	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
							YES NO
	AY	EP 0 662 705 B1	8/23/00	EPO			
	AZ	WO 98/36045	8/20/98	PCT			

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

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XX	BA	P.J. Ireland, "High Aspect Ratio Contacts: A Review of the Current Tungsten Plug Process," <i>Thin Solid Films</i> 304 (1997), pp. 1-12.
CC	BB	C. Lee and S.C. Lee, "Effects of Plasma Treatments on the Erosion of TEOS-BPSG Films by Chemical Etchants," <i>Solid State Electronics</i> , Vol. 41, No. 6, pp. 921-923 (1997).
WW	BC	M.R. Baklanov, et al., "Applicability of HF Solutions for Contact Hole Cleaning on Top of TiSi ₂ Electrochemical Society Proceedings, Vol. 97-35, pp. 602-609 (1998). <i>DEFINED</i> DEC 31 2001
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MM	BE	K. Ueno, et al., "Cleaning of CHF ₃ Plasma-Etched SiO ₂ /SiN/Cu Via Structures with Dilute Hydrofluoric Acid Solutions," <i>J. Electrochem. Soc.</i> , Vol. 144, No. 7, pp. 2565-2572 (July 1997).
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EXAMINER

DATE CONSIDERED

3-18-03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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